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Ober et al.

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(54) **AROMATIC POLYACETALS AND ARTICLES COMPRISING THEM**

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This patent is subject to a terminal disclaimer.

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CPC ***C08G 65/40*** (2013.01); ***C08G 65/38*** (2013.01); ***C08G 65/485*** (2013.01); *C08G 2650/12* (2013.01)

(58) **Field of Classification Search**
CPC C08G 65/00
USPC 568/592
See application file for complete search history.

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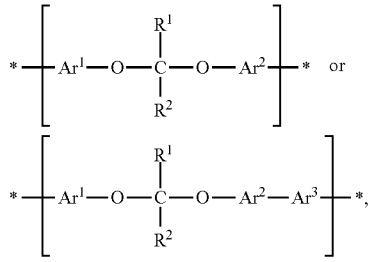
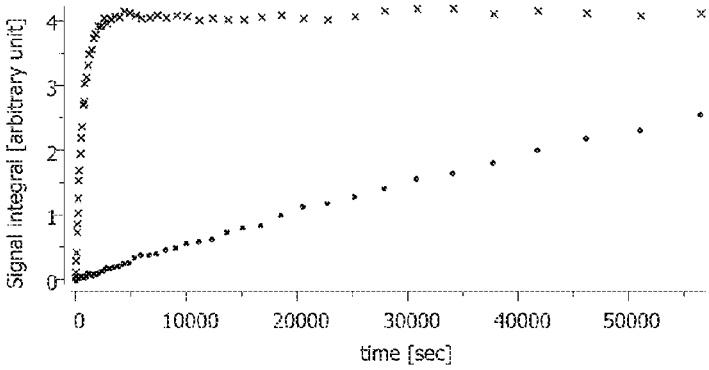
(57) **ABSTRACT**

A polymer includes repeat units having the structure



wherein R^1, R^2, Ar^1, Ar^2, and Ar^3 are defined herein. The polymer can be prepared by Suzuki polycondensation. The acetal and/or ketal functionality in the polymer backbone make the backbone-cleavable in acid. The polymer is useful in applications including lithographic photoresists.

10 Claims, 1 Drawing Sheet